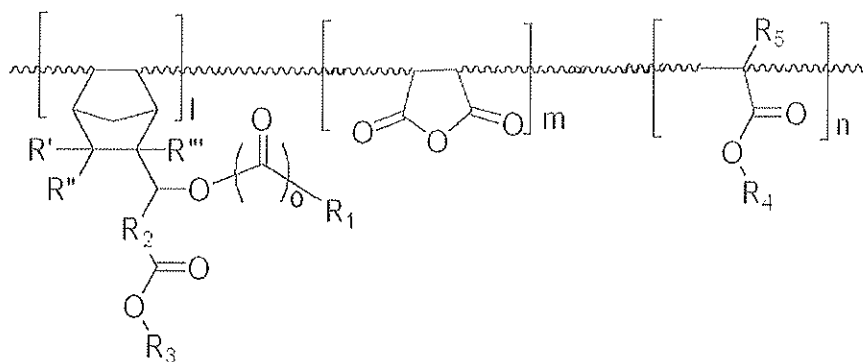


ADDITIVE FOR RESIST AND RESIST COMPOSITION COMPRISING SAME

ABSTRACT

A resist additive represented by Formula 1 below and a resist composition including the additive are disclosed. The resist additive improves hydrophobicity of the surface of a resist film to prevent materials from being leached from the resist film in water during an immersion lithography process and is stripped off by a developer during a development process to improve hydrophilicity of the surface of the resist film and allow the surface of the resist film to have a low static contact angle, so that a micropattern of the resist film with excellent sensitivity and high resolution may be formed.

Formula 1



In Formula 1, the substituents are defined as described in the specification.